L Number	Hits	Search Text	DB	Time stamp
1	1	6379492.pn.	USPAT; US-PGPUB	2004/07/19 14:01
2	3	(MgF2 or "MgF.sub.2" or (magnesium adj fluoride)) with (sputter$3 or PVD or (physical adj vapor adj deposit$3)) with (inert) with (nitrogen or N2 or "N.sub.2")	USPAT; US-PGPUB	2004/07/19 14:02
3	3	(MgF2 or "MgF.sub.2" or (magnesium adj fluoride)) with (sputter$3 or PVD or (physical adj vapor adj deposit$3)) with (nitrogen or N2 or "N.sub.2")	USPAT; US-PGPUB	2004/07/19 14:03
4	31	(MgF2 or "MgF.sub.2" or (magnesium adj fluoride)) same (sputter$3 or PVD or (physical adj vapor adj deposit$3)) same (nitrogen or N2 or "N.sub.2")	USPAT; US-PGPUB	2004/07/19 14:03
5	28	((MgF2 or "MgF.sub.2" or (magnesium adj fluoride)) same (sputter$3 or PVD or (physical adj vapor adj deposit$3)) same (nitrogen or N2 or "N.sub.2")) not ((MgF2 or "MgF.sub.2" or (magnesium adj fluoride)) with (sputter$3 or PVD or (physical adj vapor adj deposit$3)) with (nitrogen or N2 or "N.sub.2"))	USPAT; US-PGPUB	2004/07/19 14:03
6	3	(Bang.in. or Chen.in. or Venkataraman.in. or Bhatnagar.in. or (Applied adj Material).as.) and ((MgF2 or "MgF.sub.2" or (magnesium near2 fluoride) or (magnesium near2 halide) or (metal near2 fluoride)) with (coat$3 or film or layer or deposit$3 or $4CVD or apply$3)) same (density or dense or porous or porosity) same (purity or pure)	USPAT; US-PGPUB	2004/07/19 14:19
7	9	(Bang.in. or Chen.in. or Venkataraman.in. or Bhatnagar.in. or (Applied adj Material).as.) and ((MgF2 or "MgF.sub.2" or (magnesium near2 fluoride) or (magnesium near2 halide) or (metal near2 fluoride))) same (density or dense or porous or porosity) same (purity or pure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/19 14:19
8	6	((Bang.in. or Chen.in. or Venkataraman.in. or Bhatnagar.in. or (Applied adj Material).as.) and ((MgF2 or "MgF.sub.2" or (magnesium near2 fluoride) or (magnesium near2 halide) or (metal near2 fluoride))) same (density or dense or porous or porosity) same (purity or pure)) not ((Bang.in. or Chen.in. or Venkataraman.in. or Bhatnagar.in. or (Applied adj Material).as.) and ((MgF2 or "MgF.sub.2" or (magnesium near2 fluoride) or (magnesium near2 halide) or (metal near2 fluoride)) with (coat$3 or film or layer or deposit$3 or $4CVD or apply$3)) same (density or dense or porous or porosity) same (purity or pure))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/19 14:19
9	24	(Bang.in. or Chen.in. or Venkataraman.in. or Bhatnagar.in. or (Applied adj Material).as.) and ((MgF2 or "MgF.sub.2" or (magnesium near2 fluoride) or (magnesium near2 halide) or (metal near2 fluoride)) with (coat$3 or film or layer or deposit$3 or $4CVD or apply$3)) same ((corros$3 or corrod$3 or protect$3 or pit or pitted or pitting or defect$3 or damag$3) with (fluorine or NF3 or "NF.sub.3" or CHF3 or "CHF.sub.3" or heater or aluminum or Al or AlN or (aluminum adj nitride) or support or pedestal or susceptor))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/19 14:21

| 10 | 21 | ((Bang.in. or Chen.in. or Venkataraman.in. or Bhatnagar.in. or (Applied adj Material).as.) and ((MgF2 or "MgF.sub.2" or (magnesium near2 fluoride) or (magnesium near2 halide) or (metal near2 fluoride)) with (coat$3 or film or layer or deposit$3 or $4CVD or apply$3)) same ((corros$3 or corrod$3 or protect$3 or pit or pitted or pitting or defect$3 or damag$3) with (fluorine or NF3 or "NF.sub.3" or CHF3 or "CHF.sub.3" or heater or aluminum or Al or AlN or (aluminum adj nitride) or support or pedestal or susceptor))) not ((Bang.in. or Chen.in. or Venkataraman.in. or Bhatnagar.in. or (Applied adj Material).as.) and ((MgF2 or "MgF.sub.2" or (magnesium near2 fluoride) or (magnesium near2 halide) or (metal near2 fluoride))) same (density or dense or porous or porosity) same (purity or pure)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/07/19 14:21 |